K-PURE® TAG-2678 is a quaternary ammonium blocked triflic acid thermal acid generator specifically designed for use in thermally cured microlithography coatings. It has a sharp and irreversible activation profile and does not produce any volatile components upon activation. K-PURE® TAG-2678 is ideally suited for amino crosslinkable (melamine, self-condensed melamine, glycoluril, urea) or silanol and alkoxysilane crosslinkable resins. K-PURE® TAG-2678 can also be used to catalyze the polymerization of epoxy resins and ring opening polymerization of cyclic ethers as well as other monomers capable of undergoing cationic polymerization.

**ADVANTAGES:**
- Sharp Activation Profile
- No volatile by-products after activation

**TYPICAL PROPERTIES:**
- **Appearance**: White Crystals
- **Melting Point °C**: 120-121
- **Active content, %**: 100

**SOLUBILITY:**
Soluble in ethyl lactate, PGME, acetone, and propylene carbonate. Limited solubility in PGMEA. Sparsely soluble in water (~1%).

**APPLICATIONS:**
- Anti-reflective Coatings (ARC, BARC)
- Resist under layers (bilayer, trilayer resists)
- Siloxane etch stop hardmasks

**TYPICAL USAGE LEVELS:**
0.01 - 3.0 % as supplied on total resin solids.

**INCORPORATION:**
May be added directly to the formulation.

**SHELF LIFE:**
Minimum 12 months from the date of manufacture, when stored at ambient conditions in the original container.

**HANDLING & STORAGE:**
Handle with extreme care and consult the SDS for safe handling.
Best if stored tightly sealed in refrigerator.

**REGULATORY:**
Please refer to the Safety Data Sheet.